

IN THE CLAIMS:

1. **(Currently Amended)** An optical waveguide, comprising:
a silica substrate;
a first buffer layer provided on the silica substrate, the first buffer layer having a thickness of not less than 1 μm and not more than 5 μm;
at least one core provided on the first buffer layer; and
an upper cladding layer provided on the first buffer layer and covering the core,
in which wherein a thermal expansion coefficient of the first buffer layer and a thermal expansion coefficient of the upper cladding layer are substantially equal.
2. **(Currently Amended)** The optical waveguide as claimed in claim 1, wherein a refractive index of the first buffer layer is higher than a refractive index of the silica substrate.
3. **(Currently Amended)** The optical waveguide as claimed in claim 1, wherein a softening temperature of the upper cladding layer is lower than a softening temperature of the first buffer layer.
4. **(Currently Amended)** The optical waveguide as claimed in claim 2, wherein a softening temperature of the upper cladding layer is lower than a softening temperature of the first buffer layer.
5. **(Original)** The optical waveguide as claimed in claim 3, wherein at least boron (B) and phosphorus (P) are added to the upper cladding layer.

6. **(Original)** The optical waveguide as claimed in claim 4, wherein at least boron (B) and phosphorus (P) are added to the upper cladding layer.

7. **(Currently Amended)** The optical waveguide as claimed in claim 5, wherein at least germanium (Ge) is added to the first buffer layer.

8. **(Currently Amended)** The optical waveguide as claimed in claim 6, wherein at least germanium (Ge) is added to the first buffer layer.

9. **(Canceled)**

10. **(Currently Amended)** The optical waveguide as claimed in claim 1, further comprising another a second buffer layer interposed between the silica substrate and the above first buffer layer, a thermal expansion coefficient of the another second buffer layer is being between a thermal expansion coefficients of the silica substrate and the above first buffer layer.

11. **(Withdrawn)** A method of fabricating an optical waveguide, comprising the steps of:

 forming a buffer layer on a silica substrate by using a vapor phase deposition;

 forming a core layer on the buffer layer by using a vapor phase deposition;

 forming first and second cores by patterning the core layer;

 forming an upper cladding layer covering the first and second cores by using a vapor phase deposition, said upper cladding layer having a thermal expansion coefficient that is substantially equal to that of the buffer layer; and

 annealing the upper cladding layer to fluidize.

12. **(Withdrawn)** The method of fabricating an optical waveguide as claimed in claim 11, wherein the upper cladding layer are deposited and annealed with multiple steps.
13. **(New)** The optical waveguide as claimed in claim 3, wherein at least germanium (Ge) is added to the first buffer layer.
14. **(New)** The optical waveguide as claimed in claim 4, wherein at least germanium (Ge) is added to the first buffer layer.
15. **(New)** The optical waveguide as claimed in claim 10, wherein a refractive index of the first buffer layer is higher than a refractive index of the silica substrate.
16. **(New)** The optical waveguide as claimed in claim 10, wherein a softening temperature of the upper cladding layer is lower than a softening temperature of the first buffer layer.
17. **(New)** The optical waveguide as claimed in claim 15, wherein a softening temperature of the upper cladding layer is lower than a softening temperature of the first buffer layer.
18. **(New)** The optical waveguide as claimed in claim 16, wherein at least boron (B) and phosphorus (P) are added to the upper cladding layer.
19. **(New)** The optical waveguide as claimed in claim 17, wherein at least boron (B) and phosphorus (P) are added to the upper cladding layer.

20. **(New)** The optical waveguide as claimed in claim 16, wherein at least germanium (Ge) is added to the first buffer layer.

21. **(New)** The optical waveguide as contained in claim 17, wherein at least germanium (Ge) is added to the first buffer layer.

22. **(New)** The optical waveguide as claimed in claim 18, wherein at least germanium (Ge) is added to the first buffer layer.

23. **(New)** The optical waveguide as claimed in claim 19, wherein at least germanium (Ge) is added to the first buffer layer.